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(54) Plasma etching apparatus.

(57) A plasma etching apparatus comprising a susceptor (12, 14) for holding a semiconductive wafer, a cooling jacket (20) having a coolant (21) of a large cooling capacity and capable of quickly cooling said susceptor (12, 14) to an intended low temperature, a process chamber (10a) enclosing the susceptor (12, 14) and the cooling jacket (20), a gas discharging mechanism (34, 36) for evacuating the process chamber (10a), an insulating member (16) inter-

posed between the susceptor (12, 14) and the cooling jacket (20), a gas supply device (71, 80) for supplying gas to an O-ring holding groove (51, 53, 55) arranged on the interface regions (59) of the susceptor (12, 14), the insulating member (16) and the cooling section (20) and a pressure control mechanism (70) for controlling the pressure of the supplied gas.

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FIG. 4



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# EUROPEAN SEARCH REPORT

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DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
A	DATABASE WPIL Week 8949, Derwent Publications Ltd., London, GB; AN 89-359386 & JP-A-1 268 030 (HITACHI) * abstract * & US-A-5 085 750 (SORAOKA) * column 3, line 19 - column 4, line 48; figure 1 *	1,2	H01J37/32 H01L21/00
A	EP-A-0 339 580 (APPLIED MATERIALS INC) * column 16, line 9 - column 18, line 5; figure 7 *	1	
			TECHNICAL FIELDS SEARCHED (Int. Cl.5)
			H01L H01J
The present search report has been drawn up for all claims			
Place of search THE HAGUE		Date of completion of the search 28 SEPTEMBER 1992	Examiner BOLDER G.
<p><b>CATEGORY OF CITED DOCUMENTS</b></p> <p>X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document</p> <p>T : theory or principle underlying the invention E : earliest patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons &amp; : number of the same patent family, corresponding document</p>			

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